# LabAdviser update: 18/6 2020

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| Updated Subject  | Contributor | Link to the updated pages |
| **Technology Research**“Technology Development of Nanoscale Silicon Plasma Etching Process” has been updated. | **Vy H. Nguyen @Nanolab** | [Technology\_Research/Technology\_Development\_of\_Nanoscale\_Silicon\_Plasma\_Etching\_Process](http://labadviser.nanolab.dtu.dk/index.php/LabAdviser/Technology_Research/Technology_Development_of_Nanoscale_Silicon_Plasma_Etching_Process) |
| **Silicon dry etching (Pegasus 2)**Nanoscale silicon dry etching with SF6 and O2: The CORE sequence | **Vy H. Nguyen @Nanolab** | [DRIE-Pegasus/Pegasus-2/Nanoscale\_silicon\_etching\_with\_SF6\_and\_O2](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Etch/DRIE-Pegasus/Pegasus-2/Nanoscale_silicon_etching_with_SF6_and_O2) |
| **Black silicon (Pegasus 2)**Black silicon on demand is a black silicon process made from the CORE sequence | **Vy H. Nguyen @Nanolab** | [Pegasus-2/Black\_silicon\_on\_Demand](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Etch/DRIE-Pegasus/Pegasus-2/Black_silicon_on_Demand) |
| **Deposition of AlN (ALD2)**New page on AlN with NH3 plasma on ALD 2 has been made | **Evgeniy Shkondin @Nanolab** | [/Thin\_film\_deposition/ALD2\_(PEALD)/AlN\_deposition\_using\_ALD2](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/ALD2_%28PEALD%29/AlN_deposition_using_ALD2) |
| **Deposition of HfO2 (ALD2)**New section on HfO2 deposition with O2 plasma on ALD2. | **Evgeniy Shkondin @Nanolab** | [ALD2\_(PEALD)/HfO2\_deposition\_using\_ALD2#HfO2\_deposition\_using\_O2\_plasma](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/ALD2_%28PEALD%29/HfO2_deposition_using_ALD2#HfO2_deposition_using_O2_plasma) |
| **Standard recipes on ALD2**This page has been updated with ALN deposition recipe with NH3 plasma and HfO2 deposition with O2 plasma | **Evgeniy Shkondin @Nanolab** | [ALD2\_(PEALD)/Standard\_recipes\_on\_the\_ALD2\_tool](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/ALD2_%28PEALD%29/Standard_recipes_on_the_ALD2_tool) |
| **XRD at Nanolab**Restructuring this page. There are now two subpages to this page. One for each XRD at Nanolab.* XRD SmartLab
* XRD Powder

The page also has subpages about the software used (some of these pages may still be under construction):* Installing SmartLab Studio II
* Converting data from XRD Powder to SmartLab Studio II
* Guide for using SmartLab Studio II for data Analysis
* Guide for using HighScore Plus for advanced powder data analysis
 | **Kristian H. Rasmussen @Nanolab** | [/Characterization/XRD](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/XRD)* [/XRD/XRD\_SmartLab](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/XRD/XRD_SmartLab)
* [/XRD/XRD\_Powder](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/XRD/XRD_Powder)
* [/XRD/software](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/XRD/software)
* [/XRD/dataconversion](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/XRD/dataconversion)
* [/XRD/SLSII\_analysis](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/XRD/SLSII_analysis)
* [/XRD/HighScore\_analysis](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/XRD/HighScore_analysis)
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| **Stylus profilers: Dektak’s**New section on the height accuracy on the Dektak’s | **Rebecca B. Ettlinger @Nanolab** | [Characterization/Profiler#Height\_accuracy](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/Profiler#Height_accuracy) |
|  **AFM**New section on the height accuracy on the AFM | **Berit Herstrøm @Nanolab** | [/Characterization/AFM:\_Atomic\_Force\_Microscopy#Height\_Accuracy](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/AFM%3A_Atomic_Force_Microscopy#Height_Accuracy) |
| **Optical profiler**Added Sensofar presentation of the “Instrument techniques and possibilities” and leaflet with the instrument specifications. | **Berit Herstrøm @Nanolab** |  [/Characterization/Profiler#Optical\_Profiler\_.28Sensofar.29](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/Profiler#Optical_Profiler_.28Sensofar.29) |

# Equipment Manuals updated in LabManager (since 11th of May):

As an approved user on a piece of equipment you have to make sure you have read and understood the latest version of the manual before using the equipment.

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|  | **Manual for DRIE-Pegasus 1**, ver 3.3 |
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|  | **Manual for Developer: TMAH Manual**, ver 2.4 |
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|  | **Manual for AFM Icon-PT 1 & 2**, ver 4.2 |
|  | **Manual for MVD**, ver 6 |
|  | **Manual for XPS K-Alpha**, ver 4 |
|  | **Manual for XRD SmartLab**, ver 2.2 |
|  | **Manual for III-V Plassys RIE**, ver 3.2 |
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|  | **Manual for ALD 1**, ver 5 |
|  | **Manual for Aligner: Maskless 02**, ver 1.2 |
|  | **Manual for Si Etch 3: KOH**, ver 3 |
|  | **Manual for Aligner: Maskless 01**, ver 3 |
|  | **Manual for Dektak XTA**, ver 5.2 |
|  | **Manual for Oven: HMDS-2**, ver 3.1 |
|  | **Manual for Lift-off**, ver 3 |
|  | **Manual for resist strip**, ver 3 |
|  | **Manual for Aligner: Maskless 03**, ver 2 |
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|  | **Manual for Wordentec**, ver 11 |